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1 Adoption of OPC and the impact on design and layout

F. M. Schellenberg, Olivier Toublan, Luigi Capodieci, Bob Socha

June 2001 **Proceedings of the 38th conference on Design automation**

Publisher: ACM Press

Full text available: [pdf\(574.58 KB\)](#) Additional Information: [full citation](#), [abstract](#), [references](#), [citations](#), [index terms](#)

With the adoption of various combinations of resolution enhancement techniques (RET) for IC lithography, different process constraints are placed on the IC layout. The final layout used for mask production is dramatically different than the original designer's intent. To insure that EDA tools developed for applying RET techniques can have optimal performance, layout methodology must change to create a true "target" layer that represents the actual design intent. Verification of ...

Keywords: OAI, OPC, PSM, Quasar, RET, SRAF, lithography, off-axis illumination, phase-shifting, quadrupole, scattering bars

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... phase-shifting **mask**, and in ... **rim width** across the **layout** ... **layout** and tools in use). Steps 410-430 can be performed using any **optical proximity correction (OPC)** tool (current **OPC** ...
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